

DOCKET NO.: 288992US0PCT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Yasuo MATSUKI, et al.

SERIAL NO.: NEW U.S. PCT APPLICATION

FILED: HERewith

INTERNATIONAL APPLICATION NO.: PCT/JP04/15101

INTERNATIONAL FILING DATE: October 6, 2004

FOR: COMPOSITION FOR FORMING SILICON-COBALT FILM, SILICON-COBALT FILM  
AND METHOD FOR FORMING SAME**REQUEST FOR PRIORITY UNDER 35 U.S.C. 119  
AND THE INTERNATIONAL CONVENTION**Commissioner for Patents  
Alexandria, Virginia 22313


Sir:

In the matter of the above-identified application for patent, notice is hereby given that the applicant claims as priority:

**COUNTRY**  
Japan**APPLICATION NO**  
2003-356158**DAY/MONTH/YEAR**  
16 October 2003

Certified copies of the corresponding Convention application(s) were submitted to the International Bureau in PCT Application No. PCT/JP04/15101. Receipt of the certified copy(s) by the International Bureau in a timely manner under PCT Rule 17.1(a) has been acknowledged as evidenced by the attached PCT/IB/304.

Respectfully submitted,  
OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.



Norman F. Oblon  
Attorney of Record  
Registration No. 24,618  
Surinder Sachar  
Registration No. 34,423

Customer Number

**22850**

(703) 413-3000  
Fax No. (703) 413-2220  
(OSMMN 08/03)